

(J) ABSTRACT OF THE DISCLOSURE

An alignable, low-profile substrate chuck for patterning an indeterminate number of substrate panels, one at a time, adjustable in x, y and theta while on the movable platform of a stage,

comprising:

a vacuum diffuser plate;

an x-bracket with multiple supporting means and locating surfaces;

an x- y-bracket, having a slideway, mounted operatively to the x-bracket;

10 a y, theta bracket, mounted slidably in the slideway of the x-y bracket, having a central yaw shaft opening and vacuum channel;

a yaw shaft fitted within the yaw shaft opening;

a configured yaw, vacuum diffuser bracket having a peripheral channel, a top plane with a vacuum diffuser plate defining a substrate support, with a number of support islands providing support for the vacuum diffuser plate flush with the support plane; and

x, y and theta adjustment means.